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Attorney Docket No.: 28955.1048

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Serial No. 10/531,208

Confirmation No. 6424

In re Application of

MITSURU UEDA, et al.

Art Unit: 1795

Filed: April 14, 2005

Examiner: Sin J. Lee

For: Photoresist Base Material, Method for Purification Thereof, and Photoresist

**COMPOSITIONS** 

US PATENT AND TRADEMARK OFFICE Customer Service Window - Mail Stop AF Randolph Building 401 Dulany Street Alexandria, Virginia 22313-1450

DO NOT ENTER: /SL

## AMENDMENT UNDER 37 C.F.R. § 1.116

In response to the Office Action mailed December 11, 2007, please amend the aboveidentified patent application as follows:

DO NOT ENTER: /SU

Sin Lee